Electronic Patent Application Fee Transmittal						
Application Number:	10672778					
Filing Date:	26-Sep-2003					
Title of Invention:	Atomic layer deposition (ALD) method with enhanced deposition rate					
First Named Inventor:	Chih-Ta Wu					
Filer:	Daniel R. McClure					
Attorney Docket Number:	252016-3000					
Filed as Large Entity						
Utility Filing Fees						
Description		Fee Code	Quantity	Amount	Sub-Total in USD(\$)	
Basic Filing:						
Pages:						
Claims:						
Miscellaneous-Filing:						
Petition:						
Patent-Appeals-and-Interference:						
Post-Allowance-and-Post-Issuance:						
Extension-of-Time:						
Extension - 1 month with \$0 paid		1251	1	120	120	

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)				
Miscellaneous:								
Request for continued examination	1801	1	790	790				
	Tota	910						